

## EAST Search History

| Ref # | Hits     | Search Query   | DBs   | Default Operator | Plurals | Time Stamp          |
|-------|----------|--|---|------------------|---------|---------------------|
| L1    | 108495   | (induct\$3 or deduct\$3 or causat\$3 or insulat\$3 or (low\$3 adj3 (dielectric or di-electric or di electric))) near5 (constant or capacit\$3) same (less or low \$3)    | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2009/04/04<br>20:59 |
| L2    | 29211485 | @ad< "20040722" or @rlad< "20040722"   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2009/04/04<br>21:00 |
| L3    | 2442     | (first or second or third) near3 (fluoride or fluor\$3 or fluorocarbon or fluoro-carbon or carbon) near5 (substrate or wafer or semiconductor)                           | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2009/04/04<br>21:00 |
| L4    | 31171    | (fluoride or fluor\$3 or fluorocarbon or fluoro-carbon or carbon) near5 (film or layer or dielectric or di-electric or di electric) same (void or space or hole or well) | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2009/04/04<br>21:00 |
| L5    | 579      | L3 and L4  | US-PGPUB;<br>USPAT; USOCR   | OR               | ON      | 2009/04/04<br>21:00 |
| L6    | 447      | L5 and L2  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2009/04/04<br>21:01 |
| L7    | 106      | L1 and L6  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2009/04/04<br>21:01 |
| L8    | 2442     | (first or second or third) near3 (fluoride or fluor\$3 or fluorocarbon or fluoro-carbon or carbon) near5 (substrate or wafer or semiconductor)                           | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2009/04/04<br>21:02 |
| L9    | 31171    | (fluoride or fluor\$3 or fluorocarbon or fluoro-carbon or carbon) near5 (film or layer or dielectric or di-electric or di electric) same (void or space or hole or well) | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ              | ON      | 2009/04/04<br>21:02 |

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| L10 | 579   | L8 and L9   | US-PGPUB;<br>USPAT; USOCR   | OR  | ON | 2009/04/04<br>21:02 |
| L11 | 106   | L7 and L10  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/04<br>21:02 |
| L12 | 14    | ((carbon near3 fluorocarbon)<br>adj3 (film or gas or layer))<br>near5 (substrate or wafer or<br>semiconductor)          | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/04<br>21:03 |
| L13 | 0     | L12 and L11   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/04<br>21:03 |
| L14 | 34471 | 438/400-404,584-597,622-<br>624,637,672-<br>675,700,733,734,758-763,778-<br>780.ccls.                                   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/04<br>21:04 |
| L15 | 35    | L14 and L11   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/04<br>21:04 |
| L16 | 0     | L15 and (((carbon near3<br>fluorocarbon) adj3 (film or gas<br>or layer)) same (substrate or<br>wafer or semiconductor)) | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/04<br>21:05 |
| L17 | 0     | L15 and ((carbon near3<br>fluorocarbon) adj3 (film or gas<br>or layer))   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/04<br>21:05 |
| S2  | 0     | JP10-092804A  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>13:16 |
| S3  | 0     | JP 10-092804A   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>13:16 |

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| S4  | 0        | "092804".pn.  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>13:17 |
| S5  | 1        | "6524963".PN.   | US-PGPUB;<br>USPAT; USOCR   | ADJ | ON | 2009/04/01<br>13:17 |
| S6  | 1        | "20070020951".PN.   | US-PGPUB;<br>USPAT; USOCR   | ADJ | ON | 2009/04/01<br>13:23 |
| S7  | 2440     | (first or second or third) near3<br>(fluoride or fluor\$3 or<br>fluorocarbon or fluoro-carbon<br>or carbon) near5 (substrate or<br>wafer or semiconductor)                              | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>13:39 |
| S8  | 31130    | (fluoride or fluor\$3 or<br>fluorocarbon or fluoro-carbon<br>or carbon) near5 (film or layer<br>or dielectric or di-electric or di<br>electric) same (void or space or<br>hole or well) | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>13:41 |
| S10 | 2440     | (first or second or third) near3<br>(fluoride or fluor\$3 or<br>fluorocarbon or fluoro-carbon<br>or carbon) near5 (substrate or<br>wafer or semiconductor)                              | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>20:13 |
| S11 | 31130    | (fluoride or fluor\$3 or<br>fluorocarbon or fluoro-carbon<br>or carbon) near5 (film or layer<br>or dielectric or di-electric or di<br>electric) same (void or space or<br>hole or well) | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>20:13 |
| S12 | 579      | S10 and S11   | US-PGPUB;<br>USPAT; USOCR   | OR  | ON | 2009/04/01<br>20:13 |
| S13 | 0        | (first or second or third) near3<br>((carbon adj3 fluorocarbon)<br>adj3 (film or gas or layer))<br>near5 (substrate or wafer or<br>semiconductor)                                       | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>20:16 |
| S14 | 2        | (first or second or third) near3<br>(carbon adj3 fluorocarbon)<br>adj3 (film or gas or layer) same<br>(substrate or wafer or<br>semiconductor)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>20:16 |
| S15 | 29211053 | @ad< "20040722" or<br>@rlad< "20040722"   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>20:18 |

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| S16 | 447      | S12 and S15   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>20:19 |
| S17 | 14       | ((carbon near3 fluorocarbon)<br>adj3 (film or gas or layer))<br>near5 (substrate or wafer or<br>semiconductor)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>20:21 |
| S18 | 13       | S17 and S15   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>20:21 |
| S19 | 1        | (first or second or third) near3<br>((carbon adj3 fluorocarbon)<br>adj3 (film or gas or layer))<br>near5 (void or hole or space)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/01<br>20:37 |
| S20 | 2        | ("6531409" "6419985").PN.   | US-PGPUB;<br>USPAT; USOCR   | OR  | ON | 2009/04/02<br>11:54 |
| S21 | 11596    | (remov\$3 or cut\$3 or etch\$3)<br>near3 (volatil\$3 or explosiv\$3<br>or unstabl\$3) same (carbon or<br>fluorine or fluorocarbon or<br>fluoride)   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/02<br>11:58 |
| S22 | 902      | (remov\$3 or cut\$3 or etch\$3)<br>near3 (volatil\$3 or explosiv\$3<br>or unstabl\$3) same (carbon or<br>fluorine or fluorocarbon or<br>fluoride) with (void or vacuum<br>or space or hole or well) | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/02<br>11:59 |
| S23 | 29211485 | @ad< "20040722" or<br>@rlad< "20040722"   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/02<br>11:59 |
| S24 | 2442     | (first or second or third) near3<br>(fluoride or fluor\$3 or<br>fluorocarbon or fluoro-carbon<br>or carbon) near5 (substrate or<br>wafer or semiconductor)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/02<br>12:01 |
| S25 | 31171    | (fluoride or fluor\$3 or<br>fluorocarbon or fluoro-carbon<br>or carbon) near5 (film or layer<br>or dielectric or di-electric or di<br>electric) same (void or space or<br>hole or well)             | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/02<br>12:01 |

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| S26 | 579   | S24 and S25   | US-PGPUB;<br>USPAT; USOCR   | OR  | ON | 2009/04/02<br>12:01 |
| S27 | 2     | S22 and S26   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR  | ON | 2009/04/02<br>12:01 |
| S28 | 6     | ("5900290"   "6005291"  <br>"6071797"   "6091081"  <br>"6215087").PN. OR<br>("6419985").URPN.   | US-PGPUB;<br>USPAT; USOCR   | ADJ | ON | 2009/04/02<br>12:02 |
| S29 | 2     | ("5525447"   "6121162").PN.<br>OR ("6531409").URPN.   | US-PGPUB;<br>USPAT; USOCR   | ADJ | ON | 2009/04/02<br>12:03 |
| S30 | 34    | ("6215087").URPN.   | USPAT   | ADJ | ON | 2009/04/02<br>12:08 |
| S31 | 149   | ((((carbon adj3 fluoride) adj3<br>gas) or fluorocarbon adj3 film)<br>same (induct\$3 or dielectric or<br>di electric or di-electric)                      | USPAT   | ADJ | ON | 2009/04/02<br>12:15 |
| S32 | 2     | S22 and S31   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/02<br>12:15 |
| S33 | 0     | ((((carbon adj3 fluoride) adj3<br>gas) or fluorocarbon adj3 film)<br>same (induct\$3 adj3 capacity)   | USPAT   | ADJ | ON | 2009/04/02<br>12:18 |
| S34 | 0     | ((((carbon adj3 fluoride) adj3<br>gas) or fluorocarbon adj3 (film<br>or layer)) same (induct\$3 adj3<br>capacity)   | USPAT   | ADJ | ON | 2009/04/02<br>12:19 |
| S35 | 34471 | 438/400-404,584-597,622-<br>624,637,672-<br>675,700,733,734,758-763,778-<br>780.ccls.   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | ADJ | ON | 2009/04/02<br>12:30 |
| S36 | 9     | ("20040006249"  <br>"20040161946"  <br>"20040175501"  <br>"20050176230"  <br>"20060040507"  <br>"20060264059"   "6429518"  <br>"6524963"   "6593246").PN. | US-PGPUB;<br>USPAT; USOCR   | ADJ | ON | 2009/04/02<br>12:41 |

4/ 4/ 2009 9:08:31 PM

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